

### Abstract of the Disclosure

The invention relates to a particle beam system comprising a particle source (1), a mirror corrector (9, 21 to 25), and an objective lens (16). The mirror corrector comprises an electrostatic mirror (9) and a magnetic beam deflector (21, 22, 23, 24, 25), which is arranged between the particle source (1) and the electrostatic mirror (9) as well as between the electrostatic mirror (9) and the objective lens (16). The magnetic beam deflector (21, 22, 23, 24, 25) is free from dispersion for each single pass. The magnetic beam deflector (21, 22, 23, 24, 25) also comprises quadrupoles and/or quadrupole components, which are provided in such a manner that a maximum of two planes, which are conjugated with regard to the diffraction plane (28) of the objective lens (16), occur on the entire path length between the first outlet from the magnetic beam deflector (21, 22, 23, 24, 25) and from the objective lens (16).